



Future Normal in Semiconductor

2025년 2월 14일(금), 10:55-12:40

Room H(루비 I), 5층

F. Silicon and Group-IV Devices and Integration Technology 분과

O60_[FH2-F] Process-Device Characterization

좌장: 백명현 교수(강릉원주대학교), 정규원 교수(서울대학교)

<p>FH2-F-1 10:55-11:10</p>	<p>Low-Temperature Deuterium Annealing for Improved Immunity Against Hot-Carrier Injection in HKMG MOSFETs Ju-Won Yeon, Hyo-Jun Park, Tae-Hyun Kil, Moon-Kwon Lee, Eui-Cheol Yun, Min-Woo Kim, Su-Jin Jeon, Dol Sohn, A-Young Kim, Sang-Min Kang, Da-Eun Bang, and Jun-Young Park Chungbuk National University</p>
<p>FH2-F-2 11:10-11:25</p>	<p>Comprehensive Understanding of Polarization Mechanism and Low Operating Voltage by $\text{Hf}_{0.5}\text{Zr}_{0.5}\text{O}_2$ Thickness Scaling on Ge Channel Jai-Youn Jeong^{1,2}, Kyul Ko¹, Changhwan Shin², and Jae-Hoon Han¹ ¹Center for Opto-electronic Materials and Devices, KIST, ²Device and Circuit Laboratory, Korea University</p>
<p>FH2-F-3 11:25-11:40</p>	<p>Accurate Modeling of NCFET-Based Ring Oscillators Jung Su Kim and Changhwan Shin School of Electrical Engineering, Korea University</p>
<p>FH2-F-4 11:40-11:55</p>	<p>Improvement of Current Drivability Through Current Limiter Towards Bulk DTMOS with Low-Power High-Performance Operation Versatility Yeji Lim and Seongjae Cho Department of Electronic and Electrical Engineering, Ewha Womans University</p>
<p>FH2-F-5 11:55-12:10</p>	<p>Multi-Vt Engineering for Logic Devices Using Rare Earth Oxide-Based Dipole-First Approach with Various Interfacial Layer Formation Sang Kuk Han¹, Hyun Jin Lim¹, Ki Sub Kim¹, Hyo Jin Ahn¹, Yeh Been Im¹, Won Jae Choi², Young Seo Na², and Changhwan Choi^{1,2} ¹Division of Materials Science and Engineering, Hanyang University, ²Department of Semiconductor Engineering, Hanyang University</p>



제 32회 한국반도체학술대회

The 32nd Korean Conference on Semiconductors

2025년 2월 12일(수)-14일(금) | 강원도 하이원리조트

Future Normal in Semiconductor

FH2-F-6 12:10-12:25	Effects of Thermal Annealing Conditions on IGZO-Based MFMS Ferroelectric TFTs Hyeonjung Park ¹ and Changhwan Shin ² ¹ Department of Electrical and Computer Engineering, Sungkyunkwan University, ² School of Electrical Engineering, Korea University
FH2-F-7 12:25-12:40	Atomic Layer Deposition for High-Mobility and Reliable ITZO Thin Film Transistors Hyeonjin Lee ¹ , Hyeonho Gu ² , Minho Park ² , Yongwoo Lee ² , and Jimin Kwon ^{1,2} ¹ Graduate School of Semiconductor Materials and Devices Engineering, UNIST, ² Department of Electrical Engineering, UNIST